

**IN THE UNITED STATES
PATENT AND TRADEMARK OFFICE**

PATENT APPLICATION

Applicant:	Chae, et al.	Case:	APPM/8501/ETCH/DRIE
Serial No.:	10/706,902	Filed:	November 11, 2003
Examiner:	Tran, Binh X.	Group Art Unit:	1765
Conf. No.:	7748		
Title:	SELECTIVE ETCH PROCESS OF A SACRIFICIAL LIGHT ABSORBING MATERIAL (SLAM) OVER A DIELECTRIC MATERIAL		

Mail Stop: AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO OFFICE ACTION DATED JULY 18, 2006

SIR:

In response to the Office Action dated July 18, 2006, having a shortened statutory period for response expired on October 18, 2006, please enter this Response and reconsider the claims pending in the application for reasons discussed below. Although Applicant believes that no additional fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 50-3562, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.